

WHAT IS CLAIMED IS:

1. A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof as a reactant, a 20 μm film thickness of said polyimide precursor having a transmittance, at 365 nm, of at least 40%; (2) an addition-polymerizable compound; and (3) a photoinitiator.
2. The photosensitive resin composition according to claim 1, wherein the polyimide precursor is formed by reacting said oxydiphthalic acid or acid anhydride thereof with diamine.
3. The photosensitive resin composition according to claim 2, wherein said diamine is a diaminopolysiloxane.
4. The photosensitive resin composition according to claim 1, wherein said transmittance is in a range of 40%-68%.
5. The photosensitive resin composition according to claim 4, wherein the composition further includes an acryl compound having an amino group.
6. A photosensitive resin composition according to claim 1, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

7. A photosensitive resin composition according to claim 1, wherein the polyimide precursor is formed from an oxydiphthalic acid or acid anhydride thereof with a diamine.

8. A photosensitive resin composition according to claim 7, wherein said diamine is a diaminodiphenyl ether.

9. A photosensitive resin composition according to claim 7, wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl ether, 2,4'-diamino-diphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diamino- diphenyl ether.

10. A photosensitive resin composition which comprises (1) a polyimide precursor formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light, the polyimide precursor being such that a 20 μm thick film thereof has a transmittance, at 365nm, of at least 40%.

11. A photosensitive resin composition according to claim 10, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

12. A photosensitive resin composition according to claim 11, wherein said diamine is a diaminodiphenyl ether.

13. A photosensitive resin composition according to claim 10, wherein said diamine is a diaminodiphenyl ether.

14. A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound and (3) a photoinitiator, the polyimide precursor being such that a 20 μ m thick film thereof has a transmittance, at 365nm, of at least 40%.

15. The photosensitive resin composition according to claim 14, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

16. A photosensitive resin composition according to claim 14, wherein said diamine is a diaminodiphenyl ether.

17. A photosensitive resin according to claim 14, wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl ether, 2,4'-diamino-diphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diamino- diphenyl ether. --

18. A photosensitive resin composition according to claim 1, wherein said polyimide precursor is formed from the oxydiphthalic acid or acid anhydride thereof as a reactant and a diaminodiphenyl ether as a diamine reactant.